51st ANNUAL LASER DAMAGE SYMPOSIUM Proceedings

SPIE. LASER DAMAGE

LASER-INDUCED DAMAGE IN OPTICAL MATERIALS 2019

22–25 September 2019 Broomfield, Colorado

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Proceedings of SPIE, 0277-786X, v. 11173

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Author(s), "Title of Paper," in Laser-induced Damage in Optical Materials 2019, edited by Christopher W. Carr, Vitaly E. Gruzdev, Detlev Ristau, Carmen S. Menoni, MJ Soileau, Emeritus Chair, Proceedings of SPIE Vol. 11173 (SPIE, Bellingham, WA, 2019) Seven-digit Article CID Number.

ISSN: 0277-786X ISSN: 1996-756X (electronic)

ISBN: 9781510630550 ISBN: 9781510630567 (electronic)

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